



ITW

PATENT
ATTORNEY DOCKET: 46884-5429

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Seiichi NAGATA) Confirmation No.: 4585
)
Application No.: 10/551,195) Group Art Unit: 1794
)
Filed: April 27, 2007) Examiner: Jonathan C. Langman
)
For: SILICON SUBSTRATE AND)
FORMING METHOD THEREOF)
(As amended))

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Winder, Mail Stop Amendment
Alexandria, VA 22314

Sir:

RESPONSE TO RESTRICTION/ELECTION REQUIREMENT

In an Office Action dated November 13, 2008, the period for response to which runs through December 15, 2008 (December 13, 2008 being a Saturday), the Examiner required election under 35 U.S.C. §§ 121 and 372 between the claims of Group I (claims 1-5) allegedly drawn to "an article," and Group II (claims 6-12) allegedly drawn to "a method."

Applicant hereby elects Group I (claims 1-5) for examination.

Applicant respectfully requests formal examination of this application.

Applicant respectfully submits that no fee is due in connection with the filing of this response. However, if there are any fees due in connection with the filing of this response, **except** for issue fees payable under 37 C.F.R. § 1.18, the Commissioner is hereby authorized by this paper to charge any such fees during the entire pendency of this application, including fees

due under 37 C.F.R. §§ 1.16 and 1.17 which may be required and including any required extension of time fees, *or* credit any overpayment to Deposit Account No. 50-0573. This paragraph is intended to be a **CONSTRUCTIVE PETITION FOR EXTENSION OF TIME** in accordance with 37 C.F.R. § 1.136(a)(3).

Respectfully submitted,

DRINKER, BIDDLE & REATH LLP

Dated: December 9, 2008

By:



Paul A. Fournier

Registration No. 41,023

Customer No. 055694

DRINKER, BIDDLE & REATH LLP

1500 K Street, N.W., Suite 1100

Washington, D.C. 20005-1209

Tel: (202) 842-8800

Fax: (202) 842-8465